

SPIN RINSE DRYER μ SRD



The MOT μ SRD is an advanced Spin Rinse Dryer system developed by M-O-T GmbH. The μ SRD is a wet process tool designed for cleaning and drying wafers for all batch applications. The stand-alone MOT μ SRD is specially designed for easy operation and maintenance. A single cassette of wafers is placed in a stainless steel rotor. The complete buildup of the system is made of plastics (PP white) and guarantees therefore a maximal resistance against chemical attacks either of acids or bases.



Spin Rinse Dryer μ SRD

Data sheet

Wafer Sizes: up to 300mm
Applications: Rinse and Drying of Wafer Baskets

Features

- Process of Wafer Baskets (25 wafers)
- High or Low-Profile Cassettes
- Easy programming of rinse, dry and purge steps
- Balanced rotor with cassettes
- Electro polished Chamber and Rotor
- Easy exchange of Rotor

Options:

- Chamber Ionization
- DI-Reclaim
- DI Heating System
- Resistivity Monitoring
- Stainless Steel Version
- Fire suppression System for solvent application

General OPTIONS

- Automatic Handling (Robot integration)
- Execution as fume hood
- Etching and Wetting Cells
- FM 4910 proofed material

BUILD-UP

- Material: PP white,
- Door material: PVC transparent,

OPERATING ELEMENTS

- All process operating elements are integrated into the front panel,
- Easy Recipe Driven operation

